

U.S.S.N. 10/050,322

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Tsai et al.

Group Art Unit: 1756

Serial No.: 10/050,322

Examiner: N. M. Barreca

Filed: 01/15/2002

In Response to Office Action

Dated: 04/13/2005


For: A BI-LAYER PHOTORESIST DRY DEVELOPMENT AND REACTIVE
ION ETCH METHOD

Attorney Docket No.: 67,200-613

CERTIFICATE OF MAILING OR FACSIMILE TRANSMISSION

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Randy W. Tung
Printed Name


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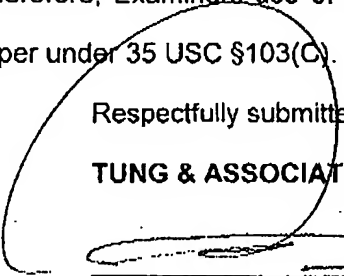
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STATEMENT OF COMMON OWNERSHIP PURSUANT TO 35 USC 103(c)

Applicants' attorney of record state that Tsai et al. (US 6,323,121 B1) and Applicants instant application were, at the time the invention was made, owned by Taiwan Semiconductor Manufacturing Company. Therefore, Examiners use of Tsai et al. as a reference in a 103(a) rejection appears to be improper under 35 USC §103(c).

Respectfully submitted,

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